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INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Applicant: Shunpei YAMAZAKI et al.

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U.S. PATENT DOCUMENTS

Examiner Initial		Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)
EL	II-5	4,905,066	02/27/90	Dohjo et al.			

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
EL	I-4	53-27483	03/14/78	Japan			Full	
EL	II-1	63-82177	04/12/88	Japan			Abst.	
EL	II-2	63-96636	04/27/88	Japan			Abst.	
EL	II-3	59-99887	06/08/84	Japan			Abst.	
EL	II-4	1-179993	07/18/89	Japan			Abst.	

OTHER DOCUMENTS (Including Author, Title, Relevant Pages, Date, Place of Publication)

EL	I-1	G. Harbeke et al., "Growth and Physical Properties of LPCVD Polycrystalline Silicon Films" J. Electrochem. Soc., March 1984, pp. 675-682						
EL	I-2	Tonouchi et al., "Characterization of μ c-Si:H Films Prepared by H_2 Sputtering," J. Journal of Applied Physics, Vol. 29, No. 3, March 1990, pp. L385-L387						
EL	I-3	Yong Sun et al., "Growth Temperature Dependence of μ c-Si:H Films Sputtered with Hydrogen Gas," J. Journal of Applied Physics, Vol. 29, No. 7, July 1990, pp. L1029-L1032						

Examiner

Date Considered

2/15/01

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.